- 2. (Amended) The process as claimed in claim 1, wherein said reaction temperature is at most equal to 150°C.
- 3. (Amended) The process as claimed in claim 1, wherein said solvent exhibits a boiling point of at least 100°C.
- 4. (Amended) The process as claimed in claim 1, wherein the reaction is carried out at a pressure such that, at the reaction temperature, the solvent is boiling.
- 5. (Amended) The process as claimed in claim 1, wherein the solvent is miscible with hydrofluoric acid which does not react with the carbamoyl fluoride.
- 6. (Amended) The process as claimed in claim 1, wherein said carbamoyl fluoride is introduced into the solvent with hydrofluoric acid.
- 7. (Amended) The process as claimed in claim 6, wherein the ratio of the hydrofluoric acid to the carbamoyl fluoride (HF/carbamoyl fluoride) is at least equal to 2.
- 8. (Amended) The process as claimed in claim 1, wherein the addition of the carbamoyl fluoride takes place gradually to a solvent heel brought to the chosen reaction temperature.

- 9. (Amended) The process as claimed in claim 1, wherein the addition is carried out at a rate such that, in the ten final 90% of the reaction duration taking place below 100°C, the molar ratio of hydrofluoric acid to isocyanate (HF acid/aromatic isocyanate) is always less than 0.5.
- 10. (Amended) The process as claimed in claim 1, wherein the carbamoyl fluoride substrate comprises an aliphatic carbon, that is sP³ hybridization, carrying at least two fluorines.
- 11. (Amended) The process as claimed in claim 10, wherein said aliphatic carbon carrying at least two fluorines is a benzyl carbon and is directly attached to an aromatic ring.
- 12. (Amended) The process as claimed in claim 11, wherein said aromatic ring is that carrying the nitrogen of the carbamoyl functional group.
- 13. (Amended) The process as claimed in claim 1, wherein the reaction mixture comprises less than 1%, with respect to the starting carbamoyl fluoride, expressed as moles, of impurities exhibiting a chlorine in the benzyl position.
- -14. (Amended) The process as claimed in claim 1, wherein the substrate corresponds to the formula:

## $(R)_m$ -Ar (- $(CX_2)_p$ -EWG)-NH-CO-F

where:

- Ar is an aromatic residue;
- the X units, which are alike or different, represent a fluorine or a radical of formula  $C_nF_{2n+1}$  with n an integer at most equal to 5;
- p represents an integer at most equal to 2;
- EWG represents a hydrocarbonaceous group or an electron-withdrawing group, the optional functional groups of which are inert under the reaction conditions.

The total carbon number of  $-(CX_2)_p$ -EWG is between 1 and 15;

- m is 0 or an integer comprising 1 to 4;
- R represents alike or different radicals comprising halogens or hydrocarbonaceous radicals.
- 15. (Amended) The process as claimed in claim 1, wherein the solvents are selected from the group consisting of chlorobenzenes, advantageously monochloro, dichloro- and trichlorobenzenes.